			TH
	Application No.	Applicant(s)	• • •
Notice of Allowability	10/539,997	FORSTER ET AL.	
	Examiner	Art Unit	
	Ida M. Soward	2822	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT I of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in 5) or other appropriate commu RIGHTS. This application is s 13 and MPEP 1308.	n this application. If not include unication will be mailed in due	ed course. <b>THIS</b>
<ol> <li>This communication is responsive to <u>interapplicants arried</u></li> <li>The allowed claim(s) is/are <u>1-9,11 and 12</u>.</li> </ol>	mament lilea saile 20, 2001.		
<ul> <li>3.</li></ul>	ve been received. ve been received in Application locuments have been received.  " of this communication to file IMENT of this application.  mitted. Note the attached EXA ves reason(s) why the oath or ust be submitted.  rrson's Patent Drawing Review  r's Amendment / Comment or  1.84(c)) should be written on the	on No  Id in this national stage applicated a reply complying with the recommendation is deficient.  AMINER'S AMENDMENT or Not declaration is deficient.  If (PTO-948) attached in the Office action of the drawings in the front (not the	quirements OTICE OF
each sheet. Replacement sheet(s) should be labeled as such in  6. DEPOSIT OF and/or INFORMATION about the dep attached Examiner's comment regarding REQUIREMENT	osit of BIOLOGICAL MATE	ERIAL must be submitted. N	Note the
Attachment(s) 1. ☑ Notice of References Cited (PTO-892)	5. ☐ Notice of In	formal Patent Application	
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Su	ummary (PTO-413),	
Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date		Mail Date Amendment/Comment	
<ol> <li>Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ol>	8. ⊠ Examiner's 9. □ Other	Statement of Reasons for Allo July 1 IDA M. SOW PRIMARY EXA	bward (

Art Unit: 2822

## **DETAILED ACTION**

This Office Action is in response to the Applicants' amendment filed June 20, 2007.

## **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Andrew Wilford on August 28, 2007.

The application has been amended as follows:

Claim 1. (currently amended) A layer sequence or structure comprising: a first highly doped n<sub>d</sub>-GaAs layer;

a graded layer of AlGaAs on the first highly doped layer and having an aluminum concentration that diminishes, starting from a boundary surface with the first highly doped layer, in the direction of an opposite boundary surface of the AlGaAs layer;

a second highly doped n<sup>+</sup>-layer; and

on at least one boundary layer of the AlGaAs layer an undoped intermediate layer juxtaposed with the respective the first or second highly doped layer and at least one boundary layer of the graded AlGaAs layer.

Art Unit: 2822

Claim 9. (currently amended) A method of making a layer sequence or structure, the method comprising the steps of:

providing a first highly doped  $n_d$ -GaAs layer as a substrate having a pair of opposite boundary surfaces,

forming on one of the boundary surfaces of the first highly doped GaAs layer an undoped GaAs layer and epitaxiing the <u>underdoped undoped</u> GaAs layer at an appropriate temperature,

providing on the undoped GaAs layer a graded AlGaAs layer; and providing on the other of the boundary surfaces a second undoped GaAs layer and epitaxiing the second undoped GaAs layer at an appropriate temperature.

Claim 12. (currently amended) A layer sequence or structure comprising a first highly doped layer,

a graded layer arranged on the first highly doped layer,

a second highly doped layer, and

en at least one boundary surface of the graded layer an undoped intermediate layer juxtaposed [[with]] between one of the highly doped layers and a boundary surface of the graded layer.

## Allowable Subject Matter

Claims 1-9 and 11-12 are allowed.

Art Unit: 2822

The following is a statement of reasons for the indication of allowable subject matter: The prior art of record does not disclose, make obvious, or otherwise suggest the structure of the applicant's together with the other limitations of the independent claims, such as:

In claim 1, "a graded layer of AlGaAs on the first highly doped layer and having an aluminum concentration that diminishes, starting from a boundary surface with the first highly doped layer, in the direction of an opposite boundary surface of the AlGaAs layer; an undoped intermediate layer juxtaposed with the first or second highly doped layer and at least one boundary layer of the graded AlGaAs layer";

In claim 9, "forming on one of the boundary surfaces of the first highly doped GaAs layer an undoped GaAs layer and epitaxiing the <u>undoped</u> GaAs layer at an appropriate temperature, providing on the undoped GaAs layer a graded AlGaAs layer; and providing on the other of the boundary surfaces a second undoped GaAs layer and epitaxiing the second undoped GaAs layer at an appropriate temperature; and

In claim 12, "an undoped intermediate layer juxtaposed between one of the highly doped layers and a boundary surface of the graded layer".

The dependent claims being further limiting and definite are also allowable.

Art Unit: 2822

## Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

The following patents are cited to further show the state of the art with respect to layer sequence semiconductor device structures:

Augusto (US 6,207,977 B1)

Koscica et al. (5,323,030)

Twynam (6,111,265)

Tyagi (US 6,249,025B1).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ida M. Soward whose telephone number is 571-272-1845. The examiner can normally be reached on Monday - Thursday 6:30am to 5:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Zandra V. Smith can be reached on 571-272-2429. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Art Unit: 2822

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information

system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Page 6

IMS

August 29, 2007

IDA M. SOWARD

PRIMARY EXAMINER